



REISSUE PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Reissue Application of

Kenji NISHI

Application No.: 08/994,758

Filed: December 19, 1997

For: PROJECTION EXPOSURE APPARATUS

Group Art Unit: 2851

Examiner: A. Mathews

Docket No.: 110157.99

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3/18/03
JPM

AMENDMENT FILED WITH RCE IN REISSUE APPLICATION

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

After entry of the Request for Continued Examination (RCE) filed herewith, please
amend this reissue application as follows:

IN THE CLAIMS:

Please cancel claim 13 without prejudice to or disclaimer of the subject matter
contained therein.

Please replace claims 9, 14, 29, 30, 33, 36, 37, 55, 68, 76, 84, 97 and 115 as follows:

9. (Three Times Amended) A scanning exposure apparatus comprising:
- a projection optical system for projecting a pattern image of a mask onto a
photosensitive substrate;
- a scanning system for synchronously scanning [a] the mask and [a] the
photosensitive substrate for scanning exposure, wherein said scanning system includes a
mask stage for scanning the mask in a direction perpendicular to an optical axis of said
projection optical system and a substrate stage for scanning the substrate in the direction
perpendicular to the optical axis, and causes the mask stage and the substrate stage to scan at

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